

ABSTRACT

Polymerizable silicon-containing compounds of formula  
5 (1) wherein R<sup>1</sup> is hydrogen, halogen or monovalent organic  
group are polymerized into polymers. A resist composition  
comprising the polymer as a base resin is sensitive to  
high-energy radiation, has excellent sensitivity and  
resolution at a wavelength of less than 300 nm, and high  
10 resistance to oxygen plasma etching, and thus lends itself to  
micropatterning for the fabrication of VLSIs.

